

## AMENDMENTS TO THE CLAIMS

**This listing of claims will replace all prior versions and listings of claims in the application:**

### **LISTING OF CLAIMS:**

1. (original): A method of manufacturing a photo mask blank by forming an opaque film or a semi-transmission film on a transparent substrate, said method comprising a step of:

forming said opaque film or said semi-transmission film onto the substrate by irradiating the substrate with an ion generated by an ion generator separately disposed in a film formation chamber during the deposition of the opaque film or the semi-transmission film on the transparent substrate by a sputtering method.

2. (currently amended): The method claimed in claim 1, wherein said step comprises:  
controlling a film stress of the opaque film or semi-transmission film formed on the substrate;

defining (a warp amount of the substrate after film formation) - (a warp amount of the substrate before the film formation) = (a warp amount of the substrate generated by the film formation); and

suppressing the warp amount of the substrate generated by the film formation to  $\pm 0.1 \mu\text{m}$  or less.

3. (original): The method claimed in claim 1, wherein said step comprises:  
directly introducing an inert gas onto the ion generator from the outside of the film formation chamber; and

ionizing said inert gas by the ion generator to irradiate the substrate with the ion.

4. (original): The method claimed in claim 1, wherein said step comprises:  
directly introducing a reactive gas into the ion generator from the outside of the film formation chamber; and

ionizing said reactive gas by the ion generator and irradiating the substrate with the ion.